

Notice of References Cited	Application/Control No. 10/537,497	Applicant(s)/Patent Under Reexamination NAKANISHI ET AL.	
	Examiner RYAN OCHYLSKI	Art Unit 4151	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-			
	B	US-			
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FOREIGN PATENT DOCUMENTS

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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	AUTHORS: Suzuki, Masao; Kasai, Hitoshi; Miura, Hirohiko; Okada, Shuji; Oikawa, Hidetoshi; Nihira, Takayasu; Fukuro, Hiroyoshi; Nakanishi, Hachiro; TITLE: Preparation of poly(amic acid) nanoparticles using the reprecipitation method and their imidization; PUBLISHER: Kobunshi Gakkai; SOURCE: Kobunshi Ronbunshu (2002), 59(10), 637-641
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
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